

# Experimental platform using high-energy nanosecond laser with XFEL at SACLA

Kohei MIYANISHI<sup>1</sup>, Keiichi SUEDA<sup>1</sup>, Yuichi INUBUSHI<sup>1,2</sup>, Toshinori YABUUCHI<sup>1,2</sup>, Tadashi TOGASHI<sup>1,2</sup>, and

Makina YABASHI<sup>1,2</sup>

<sup>1</sup>RIKEN, SPring-8 Center

<sup>1</sup>Japan Synchrotron Radiation Research Institute

# Summary

- U We have developed a new experimental platform for combinative use of XFEL and high-energy nanosecond laser, designed for high energy density science (HEDS) applications
- □ The platform is compatible with XRD, SAXS, and imaging measurements
- Users' experiments have been carried out in 2018B and 2019A with energies of up to 50 J
- Next steps are the followings;
  - Improvements in the focus profile of the laser system
  - Development of electromagnetic pulse resistant system Development of user-friendly operation scheme • Improvements of energy stability and temporal waveform controllability of the laser system

# A new experimental platform



## Beam parameters

Optical Laser Status	Operational (recently upgraded)
Pulse Energy (current)	> 50 J@10 ns
Wavelength	532 nm
<b>Repetition Rate</b>	0.1 Hz

XFEL Status	Operational
Photon Energy	4 – 20 keV
Band Width, ΔΕ/Ε	~5 × 10 <sup>-3</sup> (pink beam) ~1 × 10 <sup>-4</sup> (monochromatic beam)
Pulse Energy	~ 600 µJ @10 keV
Pulse Duration	< 10 fs
<b>Repetition Rate</b>	30 Hz
Focusing Optics	KB Mirrors for Focus (down to sub-um)
Advanced Operation	Self-Seeding, Split-and-Delay Optics, Two Colors



### Flat panel detector



#### Next steps

- Improvements in the focus profile of the laser system
  - Diffractive optical elements (flat-top profile with D=150  $\mu$ m and 250  $\mu$ m)
  - Focus monitor system with high resolution (< 2 um)</p>

1st delivery of phase plate is scheduled in early 2020 under the SACLA Basic

#### Development Program (PI: N. Ozaki of Osaka University).

The system is planned to be available for users' experiments after mid-2020. Development of electromagnetic pulses (EMP) resistant system

- Protection of electronic equipment from EMP due to high-energy lasermatter interactions
- EMP monitoring system

We have experienced malfunctions of stages and CCD cameras on >50 J shots in the first experiments after the upgrade.

- Development of user-friendly operation scheme
  - Operation system integration of optical laser and diagnostics for user experiments
- Improvements of energy stability and temporal waveform controllability of the laser system

# Acknowledgment

This development was performed in collaboration with Osaka University (Profs. N. Ozaki and R. Kodama). We thank reviewers for fruitful discussions in the "Design Review" of the chamber held during SACLA Users' Meeting 2017. We also thank Y. Tange of JASRI for helpful discussion and advice for this development.